APPLICATION

Laser Direct Imager

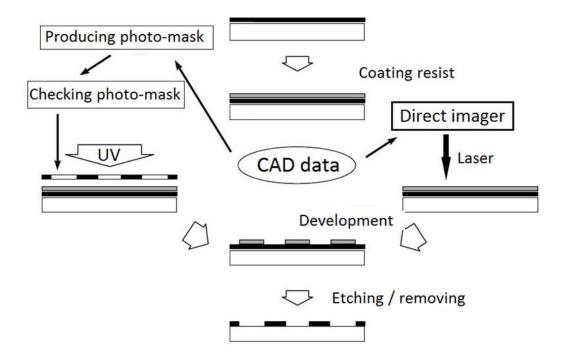
Generally, the printed circuit board is manufactured normally by producing a photo-mask first with a circuit patterns on it, and exposing the photo-mask pattern on the photosensitive material (resist) coated on the substrate with i-rays (365 nm) from a mercury lamp (photolithography) (Figure 1, left).

In contrast, the direct imaging device is a maskless exposure device which directly exposes the photosensitive material (resist) coated on the silicon substrate with a laser (Figure 1, right). In comparison with photolithography using existing masks, producing masks becomes unnecessary, and time and cost can be greatly reduced when manufacturing a small number of trials, etc.

With He-Cd laser, wavelengths 442 nm can primarily be used.

The manufacturing a printed circuit board with the direct imager is as follows.

- 1. Lightly coat a photosensitive material (resist) on the silicon substrate.
- 2. Expose the resist with the laser light (direct exposure).
- 3. The circuit pattern is created on the resist by photo development.
- 4. After the substrate is etched, the resist is removed and the substrate is completed.



photography process (previous methods / direct imaging)

